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Quantum Efficiency and Crosstalk in Subwavelength HgCdTe Dual Band Infrared Detectors

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Abstract—This work investigates the spectral quantum efficiency and inter-pixel crosstalk of a MWIR-LWIR dual band. HgCdTe-based focal plane array (FPA) photodetector (MWIR and LWIR stand for mid- and long-wavelength infrared bands). Pixels are 10 μm-wide with truncated pyramid geometry and separated by deep trenches. Three-dimensional combined full-wave electromagnetic and electrical simulations in the drift-diffusion approximation allowed to describe the complex, standing-wave-like spectral features resulting from the light interference and diffraction due to the pixels and illuminating beam aperture. The inter-pixel crosstalk for the MWIR operation demonstrated to be very sensible to the trenches depth, in contrast to the LWIR electrooptical response, left almost unchanged. The present work also investigates the causes of performance worsening in the two IR bands when pixel pitch is reduced to 5 μm, hence well below typical LWIR wavelengths and close to the diffraction limited operation.

Index Terms—Infrared detectors, HgCdTe, focal plane arrays, inter-pixel crosstalk, FDTD.

I. INTRODUCTION

A PUBLICATION by Lawson and co-workers [1] dat- ing 1959 described the outstanding properties of the variable–gap compound Hg1-xCd,xTe, which triggered an unprecedented revolution in the development of large–format infrared (IR) Focal Plane Array (FPA) detectors, so at present it is among the most widely used variable–gap semiconductors for IR photodetectors. Among these, “double–band” are photode- tectors capable to operate in two of the standard IR bands, defined as short, mid, long and very long wavelength (λ) IR bands, respectively SWIR (λ ∈ [1, 3] μm), MWIR (λ ∈ [3, 5] μm), LWIR (λ ∈ [8, 14] μm) and VLWIR (λ > 14 μm), and this capability – or, more generally, the multispectral capability – is a central requirement for third–generation, large–format infrared detectors [2], [3], [4], [5], [6], [7], [8], [9], [10], [11], [12], [13], [14].

One of the simplest schemes is known as n-p-P-n-triple layer heterostructure: each pixel includes two back-to-back p-n photodiodes with different cut-off wavelength, separated by a thin, wide bandgap layer (indicated with capital P in the scheme) acting as barrier, and a single bias contact. The detector is illuminated from below, and higher–energy photons interact with the shorter–wavelength absorber, which is located closer to the illuminated detector face. Instead, the lower–energy photons are able to reach the longer wavelength section, located above and connected to the bias contact (Fig. 1) [16], [17], [18], [19], [20], [21]. In this class of detectors, known as sequential detectors, either of the p-n junction can be reverse biased by changing the polarity of the bias voltage, obtaining the spectral response in the corresponding waveband.

The optimization of multispectral IR-FPAs requires considerable design and technology effort, and three-dimensional (3D) simulations of photodetectors with realistic pixel shape can be helpful to save time and reduce cost of fabrication, although they require large numerical resources and careful choice of computational grid [22], [23], [24], [25], [6], [26], [27].

Recent works [28], [29], [30] developed and employed multiphysics approach to reproduce single-color, compositionally graded HgCdTe IR photodetector performance, by means of combined 3D electromagnetic and electrical simulations performed with a commercial simulator by Synopsys [31], which includes an electromagnetic solver (EMW), and an electron transport solver (Sentaurus Device), employed in the drift–diffusion approximation. In those works, simulations of a 5 × 5 miniarray of pixels illuminated by a narrow Gaussian beam focused on its central pixel (CP) provided useful indications about the optimal bias point and effect of pixel geometry on the spectral quantum efficiency (QE) and inter-pixel crosstalk.

The application of the same procedure to dual-band FPAs is not straightforward, especially when heterostructures are concerned, in which carrier density drops to very small values due to reverse bias of semiconductor junctions, unfavoring fast numerical convergence. Hence, a preliminary task was the development and validation of the simulation method against dual-band detector experimental results coming from the literature, as described in detail in Ref. [15].

In the present work, we extend the investigation estimating the impact on QE and inter-pixel crosstalk induced by adopting shallower trenches and reduced pixel pitch size with respect to Ref. [15]. Motivations are twofold: first, in principle trenches should be as deep as possible, in order to prevent carriers photogenerated in a given pixel to diffuse towards neighboring ones, contributing to worsen the captured image definition. However, for technological reasons, getting very deep trenches could be challenging or even not possible.

Second, concerning possible effects, benefits and drawbacks induced by decreasing the pixel size, the scenario is more
complicated. Let us consider a lens-detector system (where a “lens” in realizations may even be a sophisticated camera objective) with focal ratio \( F = f/D \), where \( D \) and \( f \) are respectively the lens diameter and focal length. In terms of potential image resolution, the optical system performance ranges between two extrema: the diffraction-limited case, and the optics-limited case \([32],[33],[34],[9],[9],[35]\). In the first case, the optical frequency is half the sampling frequency (Nyquist criterion), i.e., the pixel pitch \( P_0 \) must be

\[
P_0 = F\lambda/2,
\]

whereas in the second case \( P_0 \) is chosen equal to the Airy disk diameter produced by the lens in the focal plane, when imaging a point-like source. The image profile is given by

\[
A(r) = 2\frac{F\lambda}{\pi r} J_1 \left(\frac{\pi r}{F\lambda}\right)
\]

where \( r \) is the radial coordinate in the focal plane and \( J_1 \) is a Bessel function of the first kind of order 1 \([36]\). Since the first zero of \( J_1(x)/x \) occurs at \( x \approx 3.832 \), i.e., \( r \approx 3.832 F\lambda/\pi = 1.22 F\lambda \), the condition

\[
P_0 = 2r \approx 2.44 F\lambda
\]

identifies an optics-limited system. Considering Eq. (1), a diffraction-limited optical system with \( F = 1 \) and \( P_0 = \lambda/2 \) should be an optimal choice \([32],[9]\). In fact, in principle it provides identical performance of a more conventional \( F = 4 \) optical system with \( P_0 \) four times wider, with the advantage of an overall smaller volume, lower weight and potentially cheaper imaging sensor. As reference values, \( P_0 \) ranging in the interval \([5,6] \) \( \mu m \) for LWIR and in the interval \([2,3] \) \( \mu m \) for MWIR have been recommended \([32],[33],[34],[9]\).

For the present work there is a further complication: we address MWIR-LWIR detectors, therefore the overall wavelength interval extends from 3 \( \mu m \) to 12 \( \mu m \); it is a hard task to find an optimal choice for \( P_0 \), keeping the same \( F = 1 \) “lens” for both IR bands. All the more reason to manage estimating the impact of different choices for \( P_0 \); therefore, we start considering first the same FPA described in Ref. \([15]\) with \( P_0 = 10 \mu m \), then we reduce \( P_0 \) to 7.5 \( \mu m \), and finally down to 5 \( \mu m \). Most likely there is a price to pay in terms of QE reduction and increased inter-pixel crosstalk, both for smaller pixel size and shallower trenches, therefore a focused study on possible limitations induced by reduced pixel pitch and shallower inter-pixel trenches is desirable.

In section II we describe the detector and the simulation methods, whereas in section III the obtained results are shown, followed by some final considerations in section IV.

II. SIMULATING A DUAL BAND DETECTOR

Our starting point is the detector described in Ref. \([15]\), modeled as the \( 5 \times 5 \) MWIR-LWIR pixels miniarray shown in Fig. 1, with pixel pitch \( P_0 = 10 \mu m \), illuminated from below by a narrow Gaussian beam centered on the miniarray CP and focused on the \( z = 0 \) illuminated face. The need for a \( 5 \times 5 \) miniarray, instead of the more common choice \( 3 \times 3 \), is justified by the increase of calculation accuracy required to describe the inter-pixel crosstalk in presence of interference effects due to internal reflections, more prominent for LWIR operation, since the wavelength is in the order of \( P_0 \) \([37],[38],[35],[39]\). The beam power flux profile at the illuminated face is \( \Phi(r) = \Phi_0 \exp (-2r^2/w_0^2) \), where \( \Phi_0 = 1 \) mW cm\(^{-2}\) is the optical power flux along the beam axis, \( r \) is the radial distance from it, and \( w_0 \) is the beam waist radius, set to 2.5 \( \mu m \) for all the simulations.

A. Detector detailed structure

The simulated MWIR-LWIR miniarray consists of a heterostructure with doping scheme \( N^+ - \nu - P^+ - \pi - N^+ \) (conventionally, lower case Greek letters refer to low-doped absorber regions, whereas upper case letters refer to layers with a bandgap wider than absorbers). It is composed by a 1.5 \( \mu m \)-thick \( \text{Hg}_0.59\text{Cd}_{0.41}\text{Te} \) \( N^+ \)-SWIR donor doped \( (N_D = 2 \times 10^{17} \text{cm}^{-3}) \).
cm$^{-3}$) contact layer grown on a CdTe substrate, followed by two $\nu$- and $\pi$-absorbers with different bandgap and doping, separated by a $P^+$-SWIR barrier, and by a 0.5 $\mu$m-thick Hg$_{0.68}$Cd$_{0.32}$Te donor-doped ($N_D = 2 \times 10^{17}$ cm$^{-3}$) cap layer. The $\nu$- and $\pi$-absorbers are respectively a 4.2 $\mu$m-thick low donor-doped ($N_D = 10^{15}$ cm$^{-3}$) Hg$_{0.705}$Cd$_{0.295}$Te (MWIR) and a 4.4 $\mu$m-thick low acceptor-doped ($N_A = 5 \times 10^{15}$ cm$^{-3}$) Hg$_{0.81}$Cd$_{0.19}$Te (LWIR) layer, and they are separated by a 0.5 $\mu$m-thick acceptor-doped ($N_A = 5 \times 10^{17}$ cm$^{-3}$) Hg$_{0.55}$Cd$_{0.45}$Te $P^+$-SWIR barrier. To provide a realistic description of the geometry, a 0.5 $\mu$m-thick transition layer with linear composition profile is inserted to connect the SWIR contact layer to the MWIR absorber, and another similar one connects the LWIR absorber to the cap layer.

Deep triangular trenches define the pixels, giving them a truncated pyramid shape with 10 $\mu$m wide square base. The angle $\theta$ of the mesa sidewalls is set to 12° with respect to the pixel vertical axis, a value that should assure total reflection at the sidewalls in a large interval of incident radiation wavevector directions [38]. A metal ring surrounds the perimeter of pixels, and it is connected to their SWIR contact layer, providing a common ground for all them. The cap layer of each pixel is connected to a square metallic layer (the bias contact) via an opening in a 0.3 $\mu$m thick CdTe passivation layer, which covers the pixel upper face.

B. Material Parameters

The dependence of HgCdTe electric and optical properties on composition, doping and temperature was taken into account according to the models reported in Ref. [35] (Table I), without including possible doping-induced plasma effects in the complex refractive index, e.g., Burstein-Moss effect and free carrier absorption, [40], [41]. Electrical simulations were obtained considering Auger (modeled as in Ref.[42]) and Shockley-Read-Hall (SRH) as generation-recombination processes, neglecting instead the radiative term. Extensive discussion about this important point can be found in Ref. [43] and references therein. SRH recombination processes were modeled as in Ref. [44] considering a lifetime around 100 $\mu$s, neglecting for simplicity trap-assisted tunneling [45], [46], [47], but keeping into account possible contributions to generation-recombination rate coming from band-to-band tunneling (BTBT), described according to the classical expression by Kane [48]

$$R_{BTBT,Kane} = \frac{np - n_i^2}{(n + n_i)(p + n_i)}AE^2 \exp \left( \frac{B}{E} \right)$$

(4)

where, for parabolic barriers, the $A$ and $B$ coefficients are [49], [50]

$$A = -\frac{q\sqrt{2m_e}}{4\pi\hbar^2}, \quad B = \frac{\pi\sqrt{m_eE_g^3}}{2\sqrt{2}\hbar}.$$ 

(5)

Here $E$, $E_g$, $m_e$, $q$ and $\hbar$ are respectively the local electric field, energy gap, electron effective mass, electron charge and reduced Planck’s constant, whereas $n_i$ is the intrinsic density, and $n$ and $p$ are the electron and hole densities, respectively. Fermi-Dirac statistics and incomplete dopant ionization were taken into account, with activation energies for HgCdTe alloys estimated according to Ref. [51], [52]. The computational box included air layers located above and below the miniarray (instead of other filling material, for simplicity), and the optical boundary conditions have been set as absorbing along $z$ (this is obtained with convolutional perfectly matching layers [53]), and periodic along $x$ and $y$, in order to mimic an infinitely extended pixel array.

C. Simulation Method

The detector was simulated in dark and under monochromatic Gaussian beam illumination as described in section II, setting the lattice temperature to $T = 230$ K. According to results obtained in Ref. [15], the optimal polarization voltage to select the MWIR and LWIR bands was found to be respectively $-0.1$ V and $0.3$ V, values that in the cited reference have been shown to avoid triggering any BTBT contribution to the dark current, taking full advantage of carrier depletion of absorbers, a requirement of central importance for IR photodetectors. A separate electromagnetic simulation followed by an electric simulation was performed for each wavelength point in the interval $\lambda_n \in [2, 12]$ $\mu$m sampled with a step of 0.1 $\mu$m, whereas the power flux along the beam axis was set constant to 1 mW cm$^{-2}$. The simulator EMW section solves the Maxwell equations according to the Finite Differences Time Domain (FDTD) method [54], [55], providing $A_{opt}$, i.e., the absorbed photon density distribution in the detector (number of absorbed photons per unit volume and time). $A_{opt}$ is obtained as the divergence of the time-averaged Poynting vector $\langle \vec{S} \rangle$ [56], [37], [57], [58]

$$A_{opt}(\lambda_n) = -\nabla \cdot \langle \vec{S}(\lambda_n) \rangle,$$

(6)

where the material complex refractive index $n_r + i\kappa$ is included in $\vec{S}$ as shown e.g. in Refs. [59], [35], Eqs. (8-10). Here $h$ is the Planck constant, and $c$ is the light velocity in vacuum. The optical generation rate distribution into the detector due to interband optical absorption is given by $G_{opt} = \eta A_{opt}$ and it enters as a source term in the electron and hole continuity equations, to be self-consistently solved with Poisson equation and Fermi distribution expressions as described in detail e.g. in Ref. [35]. The quantum yield $\eta$, defined as the fraction of absorbed photons which are converted to photogenerated electron-hole pairs, was assumed to be unitary.

The presence of layers with compositional grading along the growth direction is a complication for FDTD, which was overcome according to the method outlined in Ref. [28], which allows to treat the complex refractive index as piecewise constant. As a last remark, the staircase discretization should be fine enough to guarantee a small reflection coefficient between adjacent sublayers in the compositionally graded layers (see Ref. [28] for a discussion on this point).

D. Figures of merit

We do not address in this paper the issues connected to dark current reduction and the study of the generation-recombination mechanisms. Much effort is made by several
Fig. 2. (a) The external quantum efficiency QECP, and (b) the total inter-pixel crosstalk CNNs for the four considered trench depth variants. In the inset of panel (a) the meaning of the parameter t is shown.

research groups both from academia and industry towards the minimization of dark current, especially in view of room temperature operation, and a dedicated paper would be required to address the subject [2], [60], [61], [62], [63], [64], [65], [66], [67]. Specifically for the present photodetector, a study of the dark current, the relative importance of BTBT, the choice of SWIR barrier height for minimizing the dark current and finding the optimal bias points has been reported in Ref. [15].

The QE and the inter-pixel crosstalk are two among the main figures of merit which characterize photodetectors. The QE the i-th pixel (intended as external QE) is defined as

$$\text{QE}_i = \frac{I_{\text{ph},i}}{qN_{\text{phot},i}}$$

(7)

where $N_{\text{phot},i}$ is the photon flux through its illuminated face, treated as a simulation parameter, and $I_{\text{ph},i} = I_i - I_{\text{dark},i}$ is the net contribution to the current $I_i$ in the i-th pixel resulting from the optical photogeneration, having subtracted the dark current $I_{\text{dark},i}$.

The ratio $C_i$ between the photocurrent collected by the electrical contacts of the i-th pixel and of the CP,

$$C_i(\lambda_n) = \frac{I_{\text{ph},i}(\lambda_n)}{I_{\text{ph},\text{CP}}(\lambda_n)}$$

(8)

can be regarded as a possible definition of their total inter-pixel crosstalk. Considering in particular the nearest neighboring pixels (NNs) beside the CP, the ratio $C_{\text{NNs}}(\lambda_n)$ depends a) on carriers photogenerated in the CP diffusing to the neighboring ones (yielding a diffusive crosstalk, $D_{\text{NNs}}(\lambda_n)$), and b) on carriers directly photogenerated in the NNs by the illuminating Gaussian beam tail [35] (optical crosstalk). The latter can be defined as the ratio between carriers photogenerated in one of the NNs (with volume $V_{\text{NNs}}$) and those photogenerated in the CP (with volume $V_{\text{CP}}$)

$$\mathcal{O}_{\text{NNs}}(\lambda_n) = \frac{\int_{V_{\text{NNs}}} G_{\text{opt}}(x,y,z;\lambda_n) \, dx \, dy \, dz}{\int_{V_{\text{CP}}} G_{\text{opt}}(x,y,z;\lambda_n) \, dx \, dy \, dz},$$

(9)

whereas the separation of diffusive crosstalk can be obtained following the approach described in our previous work [39] and approximated as

$$D_{\text{NNs}} \approx \mathcal{O}_{\text{NNs}} - \mathcal{O}_{\text{NNs}},$$

(10)

having exploited the proportionality between the photocurrent and the integral of $G_{\text{opt}}$ over the pixel volume appearing in the definition of $\mathcal{O}_{\text{NNs}}$.

III. SIMULATION RESULTS: TRENCH DEPTH AND PIXEL PITCH EFFECTS

Scope of the present work is to assess the effect of reducing the trench depth (section III-A) and pixel size (section III-B) on the CP quantum efficiency QECP, $C_{\text{NNs}}(\lambda_n)$ and $\mathcal{O}_{\text{NNs}}(\lambda_n)$, without discussing limitations imposed by the etching technology, possible defects and leakage caused or favored by trenches [68], and the technological issues which arise to obtain very small pixels [51], [9].

A. Effects of inter-pixel trenches

In an ideal FPA, each pixel should be perfectly insulated from its neighbors. In planar structures this cannot be rigorously guaranteed, but a proper design of contacts and passivation layer can provide an electrical quasi-insulation. Despite this, an efficient blocking of the lateral diffusion of photogenerated carriers towards neighboring pixels is a
difficult goal to achieve, although full depleted absorbers can help to this end [29]. This is an important point, since carrier lateral diffusion contribute to blur the images obtained by the photodetector.

An efficient and immediate way to curtail diffusive crosstalk is the adoption of deep trenches between pixels, and in multispectral FPAs their adoption is unavoidable [51]. However, the practical difficulty to fabricate trenches which are deep enough to efficiently prevent carrier diffusion towards neighboring pixels can represent a limitation. Aiming at assessing the effect of the trench depth, we considered three variants of the detector simulated in Ref. [15] (hereafter named “reference”), for which the trenches are very deep, as illustrated in Fig. 1. Defining \( t \) as the distance between the trench base and the common ground metal contact, the “reference” has \( t = 0 \). Thus, we considered three alternative possibilities, with \( t = 0.5 \mu m \), \( t = 1 \mu m \), and \( t = 1.5 \mu m \), and repeated for them all the simulations described in Section II-C, obtaining the results shown in Fig. 2. Concerning the MWIR operation, a progressive increase of \( t \) makes the carriers photogenerated in the CP to diffuse more easily into the NNs, causing a substantial increase of the MWIR inter-pixel crosstalk. Instead, the MWIR spectral QE \( CP \) only undergoes a modest reduction. To get deeper insight, Fig. 3 shows the photogenerated minority carrier density (holes) in case of MWIR operation (monochromatic \( \lambda = 3.5 \mu m \) Gaussian beam illumination as described in sec. II), for the cases \( t = 0 \) (the reference case) and \( t = 1.5 \mu m \): considerable diffusion between the trench base and the ground contact is apparent only for the case \( t = 1.5 \mu m \). Regarding the LWIR operation, no significant changes have been recorded, as it can be expected by considering the quasi-equivalency of the LWIR crosstalk curves reported in Fig. 2. As a final note and with reference to Fig. 2, the case \( t \approx 0.5 \mu m \) may represent a good compromise, providing values for \( C_{NNs} \) in the order of \( 10^{-3} \) along the whole MWIR band.

### B. Effects of pixel pitch

High-performance FPAs with pixel dimensions approaching the wavelength scale (Nyquist limit) are under intense investigation [32], [33], [34], [9]. The cited works recommend FPAs with pixel size \( P_0 \) ranging between \( 5 \mu m \) and \( 6 \mu m \) for LWIR and between \( 2 \mu m \) and \( 3 \mu m \) for MWIR operation. Therefore it is important to assess the effects of the \( P_0 \) reduction, starting from the value of \( P_0 = 10 \mu m \) considered for the “reference” FPA, towards a target value of e.g. \( 5 \mu m \). Regarding trench depth, we set \( t = 0.5 \mu m \), which represents a good starting point and an acceptable trade-off between technological feasibility and expected performance (sec. III-A).

Multiphysics simulations as described in sec. II-C provided the results represented by Fig. 4, where the QE \( CP \) and the total inter-pixel crosstalk \( C_{NNs} \) are shown for \( P_0 = 5, 7.5 \) and \( 10 \mu m \). Spectra show complex, standing-wave-like spectral features, resulting from the internal backreflections and light diffraction due to the pixels and beam aperture. As expected, when \( P_0 \) is reduced, QE \( CP \) decreases and \( C_{NNs} \) increases. However, it is noticeable that the effect of \( P_0 \) becomes significant only when \( P_0 \) is decreased down to \( 5 \mu m \). In addition, Fig. 5 indicates that for the LWIR band it is \( C_{NNs} \approx O_{NNs} \): as expected, in the LWIR band the contribution to inter-pixel crosstalk coming from carriers lateral diffusion is negligible, and the whole crosstalk is due to the contribution of \( O_{NNs} \).

An important point to clarify is the behavior of \( O_{NNs} \) as function of \( \lambda \). It is quite apparent that in the LWIR band, apart from oscillations due to light internal back-reflections and the ensuing interference effects, \( O_{NNs} \) strongly grows when \( \lambda \) increases. This can be explained considering the expression for the light intensity distribution of a Gaussian beam in the paraxial approximation,

\[
I(r, z, \lambda) = I_0 \left( \frac{w_0}{w(z)} \right)^2 \exp \left(-2r^2/w^2(z, \lambda)\right),
\]

where \( I_0 \) is a normalization constant, \( w(z, \lambda) = w_0 \sqrt{1 + (z/z_R(\lambda))^2} \) and \( z_R \) is the Rayleigh distance,
given by $z_R(\lambda) = \pi w_0^2 n_r / \lambda$. Hence the optical inter-pixel crosstalk $O_{NN_s}(\lambda)$ can be approximated as

$$
\bar{O}_{NN_s}(\lambda) \approx \int_{P_0/2}^{P_0} \int_{r_0/2}^{P_0/2} \frac{I(r, z_0, \lambda)}{I(r, z_0, \lambda)}
$$

where we chose $z_0 = 5 \mu m$ (just above the pixel pyramid basis), and $n_r$ is treated just as a fitting parameter (close to the CdTe value in the LWIR band), since the light propagation takes place in air, in CdTe and HgCdTe layers with different refractive index for different wavelength values, besides the fact that multiple internal reflections occur in the pixels, affecting the effective optical path. In Fig. 5, the result of the nonlinear fitting procedure $\bar{O}$ obtained employing the Eq. (12) is reported, compared to the $O_{NN_s}(\lambda)$ and $C_{NN_s}(\lambda)$ coming from the numerical simulation. An important outcome is the fact that the inter-pixel crosstalk in the LWIR section...
cannot be easily reduced by changing the pixel geometry, since it essentially depends on the beam divergence, hence on the optics which focuses the image. Instead, metalenses, microlenses, and structured interfaces [69] can be viable ways to improve the detector performance, helping in concentrating a beam, which otherwise would considerably diverge beyond its focus plane.

IV. CONCLUSIONS

We performed multi-physics simulations of a dual band HgCdTe-based focal plane array with truncated pyramid pixels. The inter-pixel crosstalk due to carrier lateral diffusion resulted very sensible to the trench depth, but only for what concerns the MWIR band, leaving the LWIR band essentially unaffected, at least for the explored cases (see Fig. 2, parameter $t$). Regarding $\text{QE}_{\text{CP}}$, the effects of trench depth resulted quite modest for the MWIR band, and negligible for LWIR.

Concerning the pixel pitch $P_0$, we explored the cases $P_0 = 5, 7.5$ and $10 \, \mu \text{m}$, and a reduction of $P_0$ was shown to affect both operating bands. However, the effects on $\text{QE}_{\text{CP}}$ are quite modest when $P_0$ is reduced from $10 \, \mu \text{m}$ to $7.5 \, \mu \text{m}$, becoming more significant for $P_0 = 5 \, \mu \text{m}$, with a maximum reduction around 30% (Fig. 4). The effects of $P_0$ on the inter-pixel crosstalk are much more substantial, since $\mathcal{C}_{\text{NNN}}$ changes by one order of magnitude in both MWIR and LWIR bands (a little less for the latter, Fig. 5).

Furthermore, the manifest increase of $\mathcal{C}_{\text{NNN}}$ for increasing $\lambda$ in the LWIR band was shown to be totally attributable to $\mathcal{O}_{\text{NNN}}$, in turn coming from the beam divergence, which increases with increasing $\lambda$ according to Eq. (11) and the expression of $z_R(\lambda)$.

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